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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of.:	§	
	§	
Yair EIN-ELI et al	§	
	§	
Serial No.: 10/551,714	§	
	§	
Filed: July 20, 2006	§	Group Art Unit: 1793
	§	
For: COPPER CMP SLURRY COMPOSITION	§	
	§	
	§	Attorney Docket: 30579
	§	
Examiner: Pegah Parvini	§	
Mail Stop: Amendment		
Commissioner for Patents		
P.O. Box 1450		
Alexandria, VA 22313-1450		


ELECTION

Sir:

This is in response to the United States Patent and Trademark Restriction Office Action mailed December 5, 2008, which response is being made on or before January 5, 2009, and for which no extension of time fee is due.

Applicants hereby elect **Group I, namely Claims 1-36 and 53**, drawn to a composition useful for the formation of a passivating layer on a substrate.

Applicants reserve the right to file, at a later date, additional divisional applications claiming priority from the present application which are directed to the non-elected Groups.

Respectfully submitted,  
  
Martin D. Moynihan  
Registration No. 40,338

Date: January 1, 2009